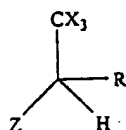


IN THE CLAIMS:

1. (Currently Amended): A photoresist composition comprising a polymeric binder, a photoactive component, a photoresist strip enhancer selected from the group consisting of alpha-trichloromethyl benzyl acetate, alpha-tribromomethyl benzyl acetate, alpha-triiodomethyl benzyl acetate, trichloromethyl allyl acetate, tribromomethyl allyl acetate, alpha-trichloromethyl benzyl propionate, alpha-tribromomethyl benzyl propionate, alpha-triiodomethyl benzyl propionate, trichloromethyl allyl propionate, tribromomethyl allyl propionate, alpha-trichloromethyl benzyl benzoate, alpha-tribromomethyl benzyl benzoate, alpha-triiodomethyl benzyl benzoate, trichloromethyl allyl benzoate, tribromomethyl allyl benzoate and alpha-bromodichloromethyl benzyl acetate and optionally a cross linking agent, wherein the photoresist enhancer is non-polymerizable with the polymeric binder, optional cross-linking agent or both and has the formula



wherein each X is independently chlorine, bromine, fluorine or iodine; Z = cyano, aryl, substituted aryl, C(Y)-R¹, C≡C-R² and C(R³)=CR⁴R⁵; Y = oxygen or sulfur; R = Z, hydrogen, (C₁-C₄)alkyl, (C₁-C₄)alkoxy, substituted (C₁-C₄)alkyl, or substituted (C₁-C₄)alkoxy; R¹ = (C¹-C⁸)alkyl, (C₁-C₈)alkoxy, substituted (C₁-C₈)alkyl, substituted (C₁-C₈)alkoxy, aryl or substituted aryl; R² = hydrogen, (C₁-C₈)alkyl, substituted (C₁-C₈)alkyl, aryl or substituted

aryl; and R³, R⁴ and R⁵ are independently selected from the group consisting of hydrogen, halogen or R¹.

2. – 4. (Cancelled).

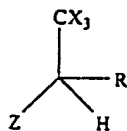
5. (Currently Amended): The composition of claim 1 wherein the photoactive component is selected from the group consisting of 9-phenylacridine, n-phenylglycine, benzophenone, N, N'-tetramethyl-4, 4'-diaminobenzophenone, N,N'-tetrethyl-4,4'-diaminobenzophenone, 4-methoxy-4'-dimethylaminobenzophenone, 3,3'-dimethyl-4-methoxybenzophenone, p,p'-bis(dimethylamino)benzophenone, p,p'-bis(diethylamino)-benzophenone, anthraquinone, 2-ethylanthraquinone, naphthaquinone, phenanthraquinone, benzoin, benzoinmethylether, benzoinethylether, benzoinisopropylether, benzoin-n-butylether, benzoin-phenylether, methylbenzoin, ethylbenzoin ~~ethylbenzoin~~, dibenzyl, benzyldiphenyldisulfide, benzyldimethylketal, 1,7-bis(9-acridinyl)heptane, 2-chlorothioxanthone, 2-methylthioxanthone, 2,4-diethylthioxanthone, 2,4-dimethylthioxanthone, 2-isopropylthioxanthone, 1,1-dichloroacetophenone, p-t-butylchloroacetophenone, 2,2-diethoxyacetophenone, 2,2-dimethoxy-2-phenylacetophenone, 2,2-dichloro-4-phenoxyacetophenone, 2-(o-chlorophenyl)-4,5-diphenylimidazole dimer, 2-(o-chlorophenyl)-4,5-di(m-methoxyphenyl imidazole dimer, 2-(o-fluorophenyl)-4,5-diphenylimidazole dimer, 2-(o-methoxyphenyl)-4,5-diphenylimidazole dimer, 2-(p-methoxyphenyl)-4,5-diphenylimidazole dimer, 2,4-di(p-methoxyphenyl)-5-phenylimidazole dimer, 2-(2,4-dimethoxyphenyl)-4,5-diphenylimidazole dimer ~~or~~ and 2-(p-methylmercaptophenyl)-4,5-diphenylimidazole dimer.

6. (Original): The composition of claim 1 wherein the polymeric binder comprises sufficient acid functionality to render said photoimageable composition developable in alkaline aqueous solution.

7. (Original): The composition of claim 6 wherein the polymeric binder has an acid number of from about 50 to about 250.

8. (Original): The composition of claim 1 wherein the photoresist strip enhancer is present in an amount up to 10% wt.

9. (Currently Amended): A method of enhancing the removal of photoresist composition from a substrate comprising the step of combining a photoresist strip enhancer selected from the group consisting of alpha-trichloromethyl benzyl acetate, alpha-tribromomethyl benzyl acetate, alpha-triiodomethyl benzyl acetate, trichloromethyl allyl acetate, tribromomethyl allyl acetate, alpha-trichloromethyl benzyl propionate, alpha-tribromomethyl benzyl propionate, alpha-triiodomethyl benzyl propionate, trichloromethyl allyl propionate, tribromomethyl allyl propionate, alpha-trichloromethyl benzyl benzoate, alpha-tribromomethyl benzyl benzoate, alpha-triiodomethylbenzyl benzoate, trichloromethyl allyl benzoate, tribromomethyl allyl benzoate and alpha-bromodichloromethyl benzyl acetate with a photoresist composition comprising a polymeric binder, a photoactive component and optionally a cross-linking agent, wherein the photoresist strip enhancer is non-polymerizable with the polymeric binder, optionally cross-linking agent or both and has the formula

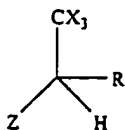


wherein each X is independently chlorine, bromine, fluorine or iodine; Z = cyano, aryl, substituted aryl, C(Y)-R¹, C≡C-R² and C(R³)=CR⁴R⁵; Y = oxygen or sulfur; R = Z, hydrogen, (C₁-C₄)alkyl, (C₁-C₄)alkoxy, substituted (C₁-C₄)alkyl, or substituted (C₁-C₄)alkoxy; R¹ = (C₁-C₈)alkyl, (C₁-C₈)alkoxy, substituted (C₁-C₈)alkyl, substituted (C₁-C₈)alkoxy, aryl or substituted aryl; R² = hydrogen, (C₁-C₈)alkyl, substituted (C₁-C₈)alkyl, aryl or substituted aryl; and R³, R⁴ and R⁵ are independently selected from the group consisting of hydrogen, halogen or R¹.

10. – 12. (Cancelled):

13. (Currently Amended): A method of manufacturing a printed wiring board comprising the steps of a) disposing on a printed wiring board substrate a photoresist composition comprising a polymeric binder, a photoactive component, a photoresist strip enhancer selected from the group consisting of alpha-trichloromethyl benzyl acetate, alpha-tribromomethyl benzyl acetate, alpha-triiodomethyl benzyl acetate, trichloromethyl allyl acetate, tribromomethyl allyl acetate, alpha-trichloromethyl benzyl propionate, alpha-tribromomethyl benzyl propionate, alpha-triiodomethyl benzyl propionate, trichloromethyl allyl propionate, tribromomethyl allyl propionate, alpha-trichloromethyl benzyl benzoate, alpha-tribromomethyl benzyl benzoate, alpha-triiodomethylbenzyl benzoate, trichloromethyl allyl benzoate, tribromomethyl allyl

benzoate and alpha-bromodichloromethyl benzyl acetate and optionally a cross-linking agent, wherein the ~~organic acid~~ photoresist strip enhancer is non-polymerizable with the polymeric binder and optional cross-linking agent and has the formula



wherein each X is independently chlorine, bromine, fluorine or iodine; Z = cyano, aryl, substituted aryl, C(Y)-R¹, C≡C-R² ~~and~~ or C(R³)=CR⁴R⁵; Y = oxygen or sulfur; R = Z, hydrogen, (C₁-C₄)alkyl, (C₁-C₄)alkoxy, substituted (C₁-C₄)alkyl, or substituted (C₁-C₄)alkoxy; R¹ = (C₁-C₈)alkyl, (C₁-C₈)alkoxy, substituted (C₁-C₈)alkyl, substituted (C₁-C₈)alkoxy, aryl or substituted aryl; R² = hydrogen, (C₁-C₈)alkyl, substituted (C₁-C₈)alkyl, aryl or substituted aryl; and R³, R⁴ and R⁵ are independently selected from the group consisting of hydrogen, halogen or R¹; b) imaging the photoresist; and c) developing the photoresist.

14. – 20. (Cancelled).